

UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/696,825	10/30/2003	Albert Hua Jeans	100200028-7	1876	
7.	7590 04/11/2005			EXAMINER	
HEWLETT-PACKARD COMPANY Intellectual Property Administration			PERALTA, GINETTE		
	P. O. Box 272400		ART UNIT	PAPER NUMBER	
Fort Collins, C	O 80527-2400		2814	· ·	
		DATE MAILED: 04/11/2005			

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)					
	10/696,825	JEAN ET AL.	(dy				
Office Action Summary	Examiner	Art Unit					
	Ginette Peralta	2814					
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply							
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be tim within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from the cause the application to become ABANDONED	nely filed s will be considered timely. the mailing date of this commun O (35 U.S.C. § 133).	nication.				
Status							
1) Responsive to communication(s) filed on							
	action is non-final.						
	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims							
4) Claim(s) 17-20 is/are pending in the application 4a) Of the above claim(s) is/are withdray 5) Claim(s) is/are allowed. 6) Claim(s) 17-20 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or	vn from consideration.						
Application Papers							
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) acce Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct	epted or b) objected to by the Edrawing(s) be held in abeyance. See	e 37 CFR 1.85(a).	121(d).				
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.							
Priority under 35 U.S.C. § 119							
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Application rity documents have been receive u (PCT Rule 17.2(a)).	on No ed in this National Stag	ie				
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal Pa)				

Application/Control Number: 10/696,825 Page 2

Art Unit: 2814

DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 17, 19-20 are rejected under 35 U.S.C. 103(a) as being unpatentable over Beckham et al. (U. S. Pat. 4,604,644) in view of Norland Optical Adhesive and HD Microsystems.

Regarding claim 17, Beckham et al. discloses in Fig. 5 a coated semiconductor substrate that comprises a semiconductor substrate 12, and a coating that comprises an organic polymerized resin material.

Beckham et al. discloses the claimed invention including a coating material but without specifying all the constituent composition.

Regarding the photopolymer, Norland discloses on page 1, ¶1, 2, and 5 that the Norland Optical Adhesive 83H (NOA83H) is a liquid adhesive curable with ultraviolet light or heat, wherein the NOA83H is taught for the disclosed intended purpose of providing a coating curable to a hard film that does not become brittle, and that has a small amount of resiliency that provides strain relief from vibrations or temperature extremes.

Art Unit: 2814

Thus, it would have been obvious to one of ordinary skill in the art at the time the invention was made to include in the coating mixture of Beckham et al. a photopolymer like NOA83H for the disclosed intended purpose of providing a coating curable to a hard film that does not become brittle, and that has a small amount of resiliency that provides strain relief from vibrations or temperature extremes.

Furthermore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to combine the photopolymer of Norland with the teachings of Beckham et al. to form a coating as it would have been beneficial because it is extremely stable and will not cure before the user desires to do so.

Regarding the adhesion promoter, HD Microsystems teaches in page 1, ¶ 1, an adhesion promoter that comprises VM-652, wherein the adhesion promoter is a compound suitable as a coating material for a semiconductor wafer; wherein the adhesion promoter is taught for the disclosed intended purpose of improving the adhesion of resin coatings to semiconductor substrates when using very low concentrations of the adhesion promoter.

Thus, it would have been obvious to one of ordinary skill in the art at the time the invention was made to combine the adhesion promoter of HD Microsystems with the curable photopolymer of Norland and the coating of Beckham et al. for the disclosed intended purpose of HD Microsystems of improving the adhesion of the coating of Beckham et al. to the substrate, and furthermore with the improved feature of

Norland of a coating that upon hardening will not become brittle and that can be permanently set when the user so desires.

Regarding claim 19, Beckham et al. as modified by Norland and HD Microsystems above, discloses that the mixture includes VM-652 and NOA83H.

Regarding claim 20, Beckham et al. as modified by Norland and HD Microsystems above, discloses a coating mixture applied to a semiconductor substrate; regarding the limitation of the coating mixture being applied using spin coating, the method of forming a device is not germane to the issue of patentability of the device itself. Therefore, this limitation has not been given patentable weight.

3. Claim 18 is rejected under 35 U.S.C. 103(a) as being unpatentable over Beckham et al. in view of Norland and HD Microsystems as applied to claims 17, 19-20 above, and further in view of Burns et al. (U. S. Pat. 5,742,075).

Beckham et al., as modified by Norland and HD Microsystems above, discloses the claimed invention with the exception of the semiconductor substrate comprising a flexible amorphous silicon coated web.

Burns et al. discloses in col. 1, lines 17-29, that amorphous silicon semiconductors when fabricated on flexible substrates have the advantage of using a number of different kinds of substrates unlike the crystalline semiconductor substrate; and the non-crystalline properties of the amorphous silicon semiconductors present the opportunity for forming very large scale devices, since the devices will not be limited

Art Unit: 2814

by the crystal and die size limitations normally associated with crystalline semiconductors.

Thus, it would have been obvious to one of ordinary skill in the art at the time the invention was made to use a flexible amorphous silicon coated flexible material, as the semiconductor substrate, for the disclosed intended purpose and the advantage of using a number of different kinds of substrates unlike the crystalline semiconductor substrate; and the non-crystalline properties of the amorphous silicon semiconductors present the opportunity for forming very large scale devices, since the devices will not be limited by the crystal and die size limitations normally associated with crystalline semiconductors.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ginette Peralta whose telephone number is (571) 272-1713. The examiner can normally be reached on Monday to Friday 8:00 AM- 5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy can be reached on (571) 272-1705. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Application/Control Number: 10/696,825 Page 6

Art Unit: 2814

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

GP

HOAI PHAM PRIMARY EXAMINER